

PHOTORESIST COMPOSITION

Patent number: JP9054432
Publication date: 1997-02-25
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Classification:
- international: G03F7/027; G03F7/038; G03F7/075; H01L21/027
- european:
Application number: JP19950210641 19950818
Priority number(s):

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Abstract of JP9054432

PROBLEM TO BE SOLVED: To improve the coating performance, soln. stability, etc., of a photoresist compsn.

SOLUTION: This compsn. contains a copolymer of a (meth)acrylate monomer having a fluoroalkyl group with an ethylenically unsatd. monomer having a silicone chain and a (meth)acrylate monomer having a polyoxyalkylene group. This compsn. does not cause unevenness in the thickness of a coating film or striation at the time of spin coating and enables uniform coating.

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